

ABSTRACT OF THE DISCLOSURE

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C1 5 In order to realize the manufacture of a  
reflection type liquid crystal display in the same  
manufacture processes as those of a transmission type  
liquid crystal display, a photolithography mask capable of  
forming both a gate electrode 22 and a reflective layer 23,  
and a photolithography mask capable of forming only the  
gate electrode 22 are prepared, and by using either one of  
10 the masks, the reflection type liquid crystal display in  
which both the gate electrode 22 and the reflective layer  
23 are formed on a transparent insulation substrate 21, and  
the transmission type liquid crystal display in which only  
the gate electrode 22 is formed are selectively  
15 manufactured.